

ABSTRACT

SPUTTERING TARGET OF FERROMAGNETIC MATERIAL WITH LOW
GENERATION OF PARTICLES

[Abstract]

5 Provided is a sputtering target of ferromagnetic material comprising a
metal having a composition containing 20 mol% or less of Cr, and Co as the
remainder; wherein the target structure includes a phase (A) which is a basis
metal, and metal phases (B) having a component composition different from the
peripheral texture within the phase (A), the area ratio occupied by oxides within
10 1 μm from the most outer periphery of metal phases (B) is 80% or less, and the
average grain size of the metal phases (B) is 10 μm or more and 150 μm or less.
Provided is a sputtering target of ferromagnetic material capable of inhibiting
the generation of particles during sputtering, and improving the pass-through
flux to achieve a stable electrical discharge with a magnetron sputtering device.

15 [Representative Figure] 1